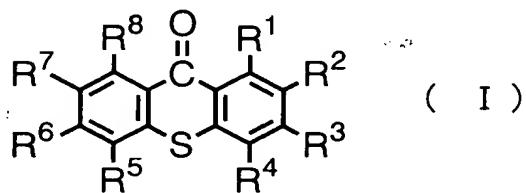


Abstract of the Disclosure

A positive resist composition, having a superior resolution as well as good resist performances such as sensitivity, depth of focus and profile, ^{is described and includes} ~~which comprises a~~ novolac resin, a radiation-sensitive quinonediazide compound and a thioxanthone compound represented by the following formula (I):



wherein R^1 , R^2 , R^3 , R^4 , R^5 , R^6 , R^7 and R^8 independently represent

10 hydrogen, halogen, alkyl, alkoxy, aryl, carboxyl or
alkoxycarbonyl ~~is provided~~.